

Supplementary Materials.

Fabrication of black aluminium thin films by magnetron sputtering

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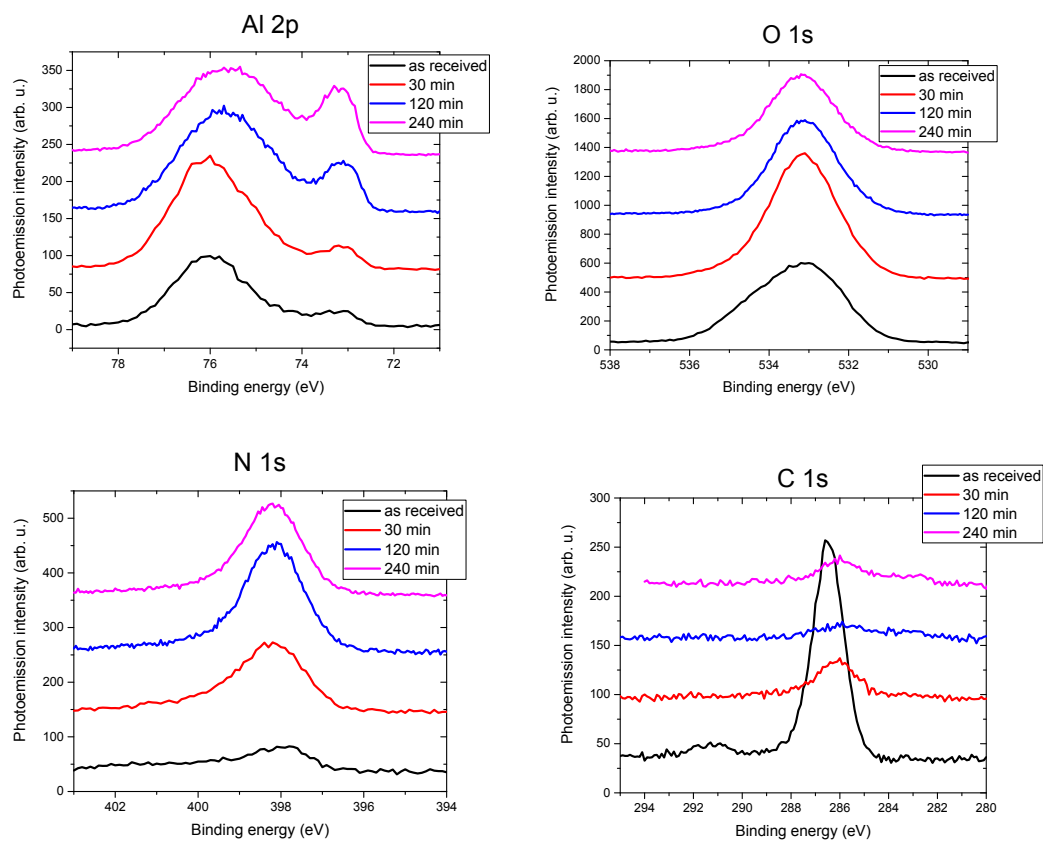


Fig. S 1 XPS spectra of B-Al 6% film a) Al 2p, b) O1s, c) N 1s, d) C 1s. The sample was sputtered with 1 keV Ar⁺ ions at a pressure of 2 Pa for 30, 120 and 240 min.